# Polyamorphism of Amorphous SiO<sub>2</sub> under Compression Based on Two-State Model

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# Abstract

Microstructure and polyamorphism of amorphous SiO<sub>2</sub> at 500 K and 0÷20 GPa were investigated by molecular dynamics simulation. The results indicate that in the studied pressure range, the network structure of amorphous SiO<sub>2</sub> includes SiO<sub>x</sub> structure units (x = 4, 5, 6) and OSi<sub>y</sub> (y = 2, 3). The two-state model (high density and low density) is used to describe the network structure of the amorphous SiO<sub>2</sub>. High-density phase is formed by SiO<sub>5</sub> and SiO<sub>6</sub> linked via OSi<sub>3</sub>, low-density phase is formed by SiO<sub>4</sub> linked via OSi<sub>2</sub>. The proportion of high density phase and low density phase depend on pressure.

Keywords: simulations, molecular dynamics, polyamorphism

# 1. Introduction

The polyamorphism is the coexistence of many amorphous states (glass or liquid), which have the same composition but different local structure and density [1]. Microstructure and polyamorphism in amorphous SiO<sub>2</sub> are investigated by both simulations [2, 3] and experiments [4, 5]. The results show that the structure of amorphous SiO<sub>2</sub> is mainly the mixture of  $SiO_x$  polyhedra (x = 4, 5, 6) under compression. Hight pressure X-ray diffraction experiment on amorphous SiO<sub>2</sub> have insighted into the structure. Sato et al. have just observed the three-dimension network structure, comprising of coner-shared SiO<sub>4</sub> tetrahedra up to 8÷10 GPa [4]. This was confirmed by using molecular dynamics (MD) simulation [3]. At higher pressure, the present of 5-fold coordination number (SiO<sub>5</sub>) and 6-fold coordination number (SiO<sub>6</sub>) correspond to the tranformation from tetrahedral network to octahedral network [5]. To clarify the changing structural process, two-state model has been developed [6]. Basing on this model, the structure of some amorphous materials such as SiO<sub>2</sub>, H<sub>2</sub>O, GeO<sub>2</sub>, P, Si, etc. can be considered comprising two phases: low density phase and high density phase. The coexistence of these phases will lead to many states which have the same chemical composition and the different densities. However, the structural details are still a matter of debate. Our previous study, we used MD simulations and visulaziation to study polyamorphism and structural transition in liquid SiO<sub>2</sub> under pressure, the structural characteristic of low and high density phases. In this study, we

continue to use the same tool to investigate the strutural transition in amorphous  $SiO_2$  under pressure. In addition, we also discuss further the relationship between structural and mechanical properties published by the other authors.

### 2. Caculation method

The  $SiO_2$  models comprising 666 silicon and 1332 oxygen particles have been generated by MD simulations with BKS (Van Beest-Kramer-Van Santen) potential and periodic boundary condition [7]. It can be described as:

$$U(r_{ij}) = \frac{q_i q_j e^2}{r_{ij}} + A_{ij} exp(-B_{ij} r_{ij}) - C_{ij} r_{ij}^{-6}$$
(1)

where  $u_{ij}$  is the interatomic potential;  $q_i$  or  $q_j$  is an effective charge of the ith atom; e is the electronic unit charge;  $r_{ij}$  is the interaction distance between atoms *i* and *j*;  $a_{ij}$ ,  $b_{ij}$  and  $c_{ij}$  are the interaction parameters (table 1). The Verlet algorithm is used to integrate the equation of motion, with the time step is 0.47 fs.

**Table 1.** Parameters of BKS potential used to modelamorphous  $SiO_2$  [8].

	A <sub>ij</sub> (eV)	B <sub>ij</sub> (Å <sup>-1</sup> )	C <sub>ij</sub> (eV Å <sup>6</sup> )	Charge (e)
0-0	1388.773	2.760	175.000	$q_0 = -1.2$
Si-O	18003.757	4.873	33.538	$q_{Si}{=}+2.4$
Si-Si	0.0	0.0	0.0	

The SiO<sub>2</sub> models are contructed at 500 K and in the  $0\div20$  GPa pressure ranges. Initial configuration is generated by placing all particles in simulation box.

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This configuration is heated to 5000 K and then cooled to 500 K. After that, the sample at 500 K and ambient pressure has been done in NPT ensemble (the constant pressure and temperature) until reaching equilibration. From this sample, we contructed samples at 500 K and different pressure. The obtained samples are relaxed in NVE ensemple (the constant volume and energy) for about  $10^6$  MD time steps. The coordination number and pair radial distribution function are caculated by averaging over 1000 last configurations seperated by 10 MD time steps.

#### 3. Results and disscution

At ambient pressure, the first peak of the Si-Si, Si-O and O-O pair radial distribution functions (PRDF) are 3.12, 1.60 and 2.60 Å, respectively. This result is in agreement with experiment in the position and height of first PRDF peaks [9].



**Fig.1.** The fraction of  $SiO_x$  (A) và  $OSi_y$  (B) in amorphous  $SiO_2$  under pressure.

The network structure of amorphous  $SiO_2$  comprises of  $SiO_x$  units that relate to short range order and  $OSi_y$  units that relate to intermediate range order. The structure units consist of a centre atom that surrounded by neighbor atoms at the cut off distance. The cut off distance used equal 2.38Å. In the 0÷20 range pressure, most of structure units are SiO<sub>x</sub> with

x=4, 5, 6 and OSi<sub>y</sub> with y=2, 3. Fig. 1a and 1b show how the fraction of structure units depend on pressure. At ambient pressure, the fraction of SiO<sub>4</sub> units and SiO<sub>5</sub> units are 96% and 4%, respectively; the fraction of SiO<sub>6</sub> units is very small (fig. 1a). As increased pressure, the fraction of SiO<sub>4</sub> units reduces to approximately 1% at 20 GPa, while the fraction of SiO<sub>6</sub> units tends to an increase, approximately 95% at 20 GPa. The fraction of SiO<sub>5</sub> units rises to maximum value in 10÷15 GPa range before tending a decrease when pressure increases.

Fig. 1b shows that the fraction of  $OSi_y$  dependens on pressure. As increased pressure, the fraction of  $OSi_2$  units reduces from 96% at ambient pressure to 1% at 20 GPa. At 8÷10 GPa, the fraction of  $OSi_2$  and  $OSi_3$  units approximately equal. Fig. 1a also shows that at threshold pressure, the fraction of SiO<sub>4</sub> units and the total fraction of SiO<sub>5</sub> and SiO<sub>6</sub> units have the same value. Therefore, as pressure increase, the decreasing fraction of SiO<sub>4</sub> units occurs simultaneouly with the decreasing fraction of  $OSi_2$  and the increasing total fraction of SiO<sub>5</sub> and SiO<sub>6</sub> units occurs simultaneouly with the increasing fraction of  $OSi_2$  and the increasing fraction of  $OSi_3$  units.

To clarify the geometry structure of structure units as pressure changes, we investigated the angle distribution and distance distribution in the SiO<sub>x</sub> and OSi<sub>y</sub> units at 0, 5 and 15 GPa (fig. 2 and 3). The results show that with each type of SiO<sub>x</sub> structure units, the O-Si-O angle distribution and Si-O bonding distance distribution are independent on pressure. Thus, the network structure of amorphous SiO<sub>2</sub> only changes in the fraction of structure units without the geometry structure of each type of units under pressure.

Next, we investigated how  $\text{SiO}_x$  structure units linked together. At atmosphere pressure, the most linkages between  $\text{SiO}_x$  structure units via one bridging oxygen atom, the kind of linkage is called the corner-sharing linkage. As pressure increase, the number of OSi<sub>3</sub> increase, which leads to increase in the number of edge-sharing linkages (linkage between  $\text{SiO}_x$  structure units via two bridging oxygen atom or face-sharing linkages (linkage between  $\text{SiO}_x$ structure units via three bridging oxygen atom), see table 2. This result show that the amorphous  $\text{SiO}_2$ structure becomes more tightly packed.

We visualized the  $SiO_2$  network structure at 5 and 15 GPa (fig. 4). The yellow domain is formed by  $SiO_4$  linked through OSi<sub>2</sub>. The distribution of this domain is not uniform. The yellow domain dominates at low pressure (or low density) and called low density phase. The black domain is cluster of  $SiO_5$ and  $SiO_6$  linked together through OSi<sub>3</sub>. At high pressure, this domain expands and dominates. So, the structure of amorphous  $SiO_2$  at high pressure (or high density) is mainly formed by the black domain, that called high density phase. The result indicates that the the structure of amorphous  $SiO_2$  seem to be similar to the structure of liquid  $SiO_2$  [10]. It was also shown in

previous experiments [11]. The compression mechanism in amorphous  $SiO_2$  may be closely related to those in liquid  $SiO_2$ . There is also transition from the low density phase to high density phase corresponding to the transition from  $OSi_2$  to  $OSi_3$  linkages, under pressure.



Fig. 2. The angle distribution O-Si-O (a) and the bonding distance distribution O-Si (b) of SiO<sub>x</sub>.



Fig. 3. The angle distribution Si-O-Si (a) and the bonding distance distribution O-Si (b) of OSi<sub>y</sub>.



**Fig. 4.** The distribution of  $SiO_x$  and  $OSi_x$  at 5 and 15 GPa.The yellow domain is cluster of  $SiO_4$  linked together through  $OSi_2$ . The black domain is cluster of  $SiO_5$  and  $SiO_6$  linked together through  $OSi_3$ .

**Table 2.** The number of  $OSi_3$ ,  $N_e$  and  $N_f$  in amorphous  $SiO_2$ .  $N_e$  is the number of edge-sharing linkages,  $N_f$  is the number of face-sharing linkages.

P(GPa)	0	5	10	15
OSi <sub>3</sub>	64	1007	1772	2034
Ne	21	560	1054	1229
$N_{f}$	1	17	69	72

Some studies using MD simulation showed that the relationship between structural and mechanical properties [12-14]. The strain at fracture increases from 10.5% to 24.1% when pressure increases from 0 to 15 GPa [12]. Other studies also indicated the transition from elastic to plastic behavior at 8÷10 GPa [13, 14]. Under pressure, the samples display more plastic before fracture. The apprearance of 5-fold coordination during compression have been shown to be responsible for the enhanced dutility in amorphous SiO<sub>2</sub> [12, 14]. 5-fold Si atoms tend to stay closer together and the clusters of 5-fold Si atoms are not uniformly distributed throughout the sample. While, Davila et al. showed that the transition between elastic and plastic behavior is correlated to changes in the ring size distribution, which characterizes the intermediate range order of these amorphous materials [13].

In this study, 5-fold coordination plays an intermediate role in the convertion from 4-fold coordination into 6-fold coordination (Fig. 1b). The changing of intermediate range order leads to more and more tightly packed structure at high pressure. At 8÷10 GPa is an important pressure threshold. At this value, we observe the change in the correlation between the proportion of structure units. This leads to the domination of low density phase at below the pressure threshold and the domination of hight density phase at above the pressure threshold. So, the structural origins of enhanced ductility and the transition between elastic and plastic behavior in amorphous SiO<sub>2</sub> can be attributed to the change of proportion of low density phase and high density phase in this material under compression.

### 4. Conclusion

Using MD simulation, we show that the network structure of amorphous SiO<sub>2</sub> is formed by five structure units, SiO<sub>x</sub> units (with x = 4, 5, 6) and OSi<sub>y</sub> units (with y = 2, 3). The network structure divides into two phases: low density phase and high density phase. The low density phase consists of SiO<sub>4</sub> linked through OSi<sub>2</sub>, high density phase consisting of SiO<sub>5</sub> and SiO<sub>6</sub> linked through OSi<sub>3</sub>. As pressure increases, there is a structure transition from the low density phase to the high density phase. The low density phase to the high density phase. The low density phase dominates at below  $8\div10$  GPa, and the high

density phase dominates above  $8 \div 10$  GPa. The structural transition is the structural origins which is responsible for the enhanced ductility in amorphous SiO<sub>2</sub> under pressure.

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